

18EC33

## Third Semester B.E. Degree Examination, Jan./Feb. 2021 Electronic Devices

Time: 3 hrs .
Max. Marks: 100

## Note: Answer any FIVE full questions, choosing ONE full question from each module.

## Module-1

1 a. Write the figures of the resulting orbitals when isolated atoms brought together and explain the characteristics.
(10 Marks)
b. Obtain the relationship between mobility and hall coefficient in a p-type bar placed in a magnetic field in the Z-direction.
(10 Marks)

## OR

2 a. Derive the equation which relates current density and mobility in a semiconductor in an applied electric field.
( 10 Marks)
b. A silicon bar $2 \mu \mathrm{~m}$ long and $200 \mu \mathrm{~m}^{2}$ in cross sectional area is doped with $1.5 \times 10^{17} / \mathrm{cm}^{3}$ phosphorus. Find the current at 300 K with 30 V applied voltage. How long does it take an average electron to drift $2 \mu \mathrm{~m}$ in pure silicon at an electric field of $80 \mathrm{~V} / \mathrm{cm}$ ? Also calculate the time required at $10^{5} \mathrm{~V} / \mathrm{cm}$. Assume mobility of electrons is $0.1350 \mathrm{~m}^{2} / \mathrm{Vsec}$. Also assume that saturation of electron drift velocity for silicon is $10^{7} \mathrm{~cm} / \mathrm{s}$ for the electric field above $10^{5} \mathrm{~V} / \mathrm{cm}$.
(10 Marks)

## Module-2

3 a. Show the effect of bias at a pn junction on transition region width, electric field, electrostatic potential, energy band diagram partic flow and current direction under the following conditions:
i) Equilibrium
ii) Forward bias
iii) Reverse bias.
(10 Marks)
b. Illustrate the care and issues to be considered in the design of solar cells.

## OR

4 a. Explain Avalanche break down and obtain equation for the electron multiplication factor.
(10 Marks)
b. Derive the relationship between the open circuit voltage and optic generation rate starting from the expression for the optically generated illuminated pn junction.
(10 Marks)

## Module-3

5 a. Show the hole and electron flow in a pnp transistor with proper biasing.
(08 Marks)
b. For the circuit shown in Fig.Q.5(b) calculate $\beta, \mathrm{I}_{\mathrm{B}}$ and $\mathrm{I}_{\mathrm{C}}$. Given that $\tau_{\mathrm{p}}=18 \mu \mathrm{~s}$, and $\tau_{\mathrm{t}}=0.2 \mu \mathrm{~s}$. What happens to the output current when $\mathrm{I}_{\mathrm{B}}$ increases and $\beta$ increases?

Fig.Q.5(b)

(06 Marks)
c. Explain the concept of base narrowing in a $\mathrm{p}^{+}-\mathrm{n}-\mathrm{p}^{+}$transistor.
(06 Marks)

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## OR

6 a. Obtain the Ebers-Moll equations and represent the same in the model form.
b. Describe the switching effects in a CE transistor circuit.

## Module-4

7 a. Analyze the effect on gate-to-channel-space charge region and IV characteristics for the following conditions in a JFET:
i) Zero gate voltage of a small drain voltage
ii) Zero gate voltage of a large drain voltage
iii) Small $V_{D S}$ value and small reverse-biased gate voltage.
(10 Marks)
b. Draw the energy band diagram in an MOS capacitor structure for the following cases:
i) p-type substrate for a positive gate bias
ii) p-type substrate for a large positive gate bias
iii) n-type substrate for a positive gate bias.
(10 Marks)

## OR

8 a. Write the small signal equivalent circuit of a JFET, ideal low frequency small signal equivalent circuit and ideal equivalent circuit including $r_{s}$.
(10 Marks)
b. Show the channel formation in the MOS structure and $I_{D}$ versus $V_{D S}$ curve for the following cases:
i) $\quad V_{g s}>V_{t}$ and small $V_{D S}$ value
ii) $\quad V_{\mathrm{gs}}>V_{\mathrm{t}}$ and large $\mathrm{V}_{\mathrm{DS}}$ value
iii) $\mathrm{V}_{\mathrm{gs}}>\mathrm{V}_{\mathrm{t}}$ and $\mathrm{V}_{\mathrm{DS}}=\mathrm{V}_{\mathrm{DS}}$ (sat)
(10 Marks)

## Module-5

9 a. What are the fabrication steps used in the fabrication of pn junctions?
b. With figures, describe the complementary MOS structure.

## OR

10 a. Illustrate the evolution of integrated circuits.
b. Explain the formation of resistors in integrated circuits.
(10 Marks)
(10 Marks)

